Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A method of manufacturing a mask comprising:

attaching to a ~~first substrate~~frame having an opening a ~~second substrate~~screen plate having a plurality of penetrating holes arranged to form a mask pattern such that the penetrating holes are positioned within the opening, the penetrating holes set to ~~be perpendicular~~perpendicularly ~~to a~~ connect holes formed in opposite ~~surface~~surfaces of the ~~second substrate~~screen plate;

forming a groove on at least one of a surface of the ~~first substrate~~frame facing the ~~second substrate~~screen plate and a surface of the ~~second substrate~~screen plate facing the ~~first substrate~~frame; and

utilizing the groove to form a flow path between the ~~first and second substrates~~frame and the screen plate.

2. (Original) The manufacturing method of the mask as defined in claim 1, wherein at least part of the groove is formed around the opening.

3. (Currently Amended) The manufacturing method of the mask as defined in claim 1,

wherein the ~~first and second substrates~~frame and the screen plate are joined by anode coupling.

4. (Currently Amended) The manufacturing method of the mask as defined in claim 2,

wherein the ~~first and second substrates~~frame and the screen plate are joined by anode coupling.

5. (Currently Amended) The manufacturing method of the mask as defined in claim 1, wherein the steps of forming the ~~second substrate~~screen plate includes:

forming the penetrating holes in a silicon wafer; and

cutting the silicon wafer into a shape corresponding to the ~~second substrate~~screen plate.

6. (Currently Amended) The manufacturing method of the mask as defined in claim 1, further comprising:

forming a magnetic film over the ~~second substrate~~screen plate.

7. (Currently Amended) The manufacturing method of the mask as defined in claim 1, wherein:

a plurality of the ~~second substrates~~screen plates are attached to the ~~first substrate~~frame;

the ~~first substrate~~frame has a plurality of the openings; and

each of the ~~second substrates~~screen plates is attached to corresponding one of the openings.

8. (Currently Amended) The manufacturing method of the mask as defined in claim 7, further comprising:

polishing surfaces of the ~~second substrate~~screen plates attached to the ~~first substrate~~frame to have a uniform height.

9. (Currently Amended) A mask comprising:

a ~~first substrate~~frame having an opening; and

a ~~second substrate~~screen plate attached to the ~~first substrate~~frame and having a plurality of penetrating holes arranged to form a mask pattern, the penetrating holes set to ~~be perpendicular~~perpendicularly ~~to a~~ connect holes formed in opposite ~~surface~~surfaces of the ~~second substrate~~screen plate, wherein:

the ~~second substrate~~screen plate is attached to the ~~first substrate~~frame such that the penetrating holes are positioned within the opening;

a groove is formed on at least one of a surface of the ~~first substrate~~frame facing the ~~second substrate~~screen plate and a surface of the ~~second substrate~~screen plate facing the ~~first substrate~~frame; and

the groove is utilized to form a flow path between the ~~first and second substrates~~frame and the screen plate.

10. (Original) The mask as defined in claim 9, wherein at least part of the groove is formed around the opening.

11. (Currently Amended) The mask as defined in claim 9, wherein the ~~first and second substrates~~frame and the screen plate are joined by anode coupling.

12. (Currently Amended) The mask as defined in claim 10, wherein the ~~first and second substrates~~frame and the screen plate are joined by anode coupling.

13. (Currently Amended) The mask as defined in claim 9, wherein a magnetic film is formed over the ~~second substrate~~screen plate.

14. (Currently Amended) The mask as defined in claim 9, wherein:

a plurality of the openings are formed in the ~~first substrate~~frame;

a plurality of the ~~second substrates~~screen plates are attached to the ~~first substrate~~frame; and

each of the ~~second substrates~~screen plates is attached to corresponding one of the openings.

15. (Currently Amended) The mask as defined in claim 14, wherein surfaces of the ~~second substrates~~screen plates attached to the ~~first substrate~~frame are polished to have a uniform height.

16. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 9; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

17. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 10; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

18. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 11; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

19. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 12; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

20. (Original) An electro-luminescence device manufactured by the method as defined in claim 16.

21. (Original) An electronic instrument having the electro-luminescence device as defined in claim 20.

22. (Currently Amended) A method of manufacturing a mask comprising:

attaching to a ~~first substrate~~frame having an opening a ~~second substrate~~screen plate having a plurality of penetrating holes arranged to form a mask pattern such that the penetrating holes are positioned within the opening, the penetrating holes set to be tapered;

forming a groove on at least one of a surface of the ~~first substrate~~frame facing the ~~second substrate~~screen plate and a surface of the ~~second substrate~~screen plate facing the ~~first substrate~~frame; and

utilizing the groove to form a flow path between the ~~first and second substrates~~frame and the screen plate.

23. (Original) The manufacturing method of the mask as defined in claim 22, wherein at least part of the groove is formed around the opening.

24. (Currently Amended) The manufacturing method of the mask as defined in claim 22, wherein the ~~first and second substrates~~frame and the screen plate are joined by anode coupling.

25. (Currently Amended) The manufacturing method of the mask as defined in claim 23, wherein the ~~first and second substrates~~frame and the screen plate are joined by anode coupling.

26. (Currently Amended) The manufacturing method of the mask as defined in claim 22, wherein the steps of forming the ~~second substrate~~screen plate includes:

forming the penetrating holes in a silicon wafer; and

cutting the silicon wafer into a shape corresponding to the ~~second substrate~~screen plate.

27. (Currently Amended) The manufacturing method of the mask as defined in claim 22, further comprising:

forming a magnetic film over the ~~second substrate~~screen plate.

28. (Currently Amended) The manufacturing method of the mask as defined in claim 22, wherein:

a plurality of the ~~second substrates~~screen plates are attached to the ~~first substrate~~frame;

the ~~first substrate~~frame has a plurality of the openings; and

each of the ~~second substrates~~screen plates is attached to corresponding one of the openings.

29. (Currently Amended) The manufacturing method of the mask as defined in claim 28, further comprising:

polishing surfaces of the ~~second substrates~~screen plates attached to the ~~first substrate~~frame to have a uniform height.

30. (Currently Amended) A mask comprising:

a ~~first substrate~~frame having an opening; and

a ~~second substrate~~screen plate attached to the ~~first substrate~~frame and having a plurality of penetrating holes arranged to form a mask pattern, the penetrating holes set to be tapered, wherein:

the ~~second substrate~~screen plate is attached to the ~~first substrate~~frame such that the penetrating holes are positioned within the opening;

a groove is formed on at least one of a surface of the ~~first substrate~~frame facing the ~~second substrate~~screen plate and a surface of the ~~second substrate~~screen plate facing the ~~first substrate~~frame; and

the groove is utilized to form a flow path between the ~~first and second substrates~~frame and the screen plate.

31. (Original) The mask as defined in claim 30, wherein at least part of the groove is formed around the opening.

32. (Currently Amended) The mask as defined in claim 30, wherein the ~~first and second substrates~~frame and the screen plate are joined by anode coupling.

33. (Currently Amended) The mask as defined in claim 31, wherein the ~~first and second substrates~~frame and the screen plate are joined by anode coupling.

34. (Currently Amended) The mask as defined in claim 30, wherein a magnetic film is formed over the ~~second substrate~~screen plate.

35. (Currently Amended) The mask as defined in claim 30, wherein:

a plurality of the openings are formed in the ~~first substrate~~frame;

a plurality of the ~~second substrates~~ screen plates are attached to the ~~first substrate~~frame; and

each of the ~~second substrates~~screen plates is attached to corresponding one of the openings.

36. (Currently Amended) The mask as defined in claim 35, wherein surfaces of the ~~second substrates~~ screen plates attached to the ~~first substrate~~frame are polished to have a uniform height.

37. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 30; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

38. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 31; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

39. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 32; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

40. (Original) A method of manufacturing an electro-luminescence device comprising:

forming a film of a light emitting material using the mask as defined in claim 33; and

cooling the mask by causing a fluid to flow through the flow path of the mask, in the step of forming a film of a light emitting material.

41. (Original) An electro-luminescence device manufactured by the method as defined in claim 37.

42. (Original) An electronic instrument having the electro-luminescence device as defined in claim 41.